



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 10/050,334
Filing Date January 15, 2002
Inventor Vishnu K. Agarwal et al.
Assignee Micron Technology, Inc.
Group Art Unit 2813
Examiner Yennhu B Huynh
Attorney's Docket No. MI22-1913
Title: Capacitor Fabrication Methods and Capacitor Constructions and
Enhanced Surface

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References – See Attached Form PTO-1449

In compliance with 37 C.F.R. §§ 1.56, 1.97 and 1.98, your attention is directed to the United States patents and other references listed on the attached Form PTO-1449. No admission is made regarding whether all the submitted references are prior art.

Citation of these references is respectfully requested.

Respectfully submitted,

Dated: 11 Jul 2005

By:


James E. Lake
Reg. No. 44,854

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Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE			ATTY. DOCKET NO. MI22-1913		SERIAL NO. 10/050,334		
		LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)			APPLICANT: Vishnu K. Agarwal et al.				
					FILING DATE January 15, 2002		GROUP 2813		
U.S. PATENT DOCUMENTS									
*Examiner's Initials		Document Number	Date	Name		Class	Subclass	Filing Date If Appropriate	
	AA	6,359,295 B2	03/2002	Yang et al.					
	AB	6,403,156	06/2002	Jang					
	AC	6,596,602 B2	07/2003	Lizuka et al.					
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	AE	6,664,186 B1	12/2003	Callegari et al.					
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	AH	2002/0142488	10/2002	Hong, Suk-Kyoung					
	AI	2002/0109198 A1	08/2002	Yang et al.					
FOREIGN PATENT DOCUMENTS									
		Document Number	Date	Country		Class	Subclass	Translation	
	AJ	KR 2002046433	05/2003	Lee, J.W.				Yes	No
	AK	EP 1 508 906 A2	02/2005	Lee et al.					
	AL								
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)									
	AM		Ritala et al.; Perfectly Conformal TiN and Al2O3 Films Deposited by Atomic Layer Deposition; Chemical						
			Vapor Deposition, v. 5, No. 1, 1999, pp. 7-9.						
	AN								
	AO								
EXAMINER		DATE CONSIDERED							
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>									